

Figure 1. (a) Photograph of patterned Electrode A composed of 13 slits with different widths and spacings. (b) Photo taken through transparent substrate showing ignition of plasma within slits of electrode.

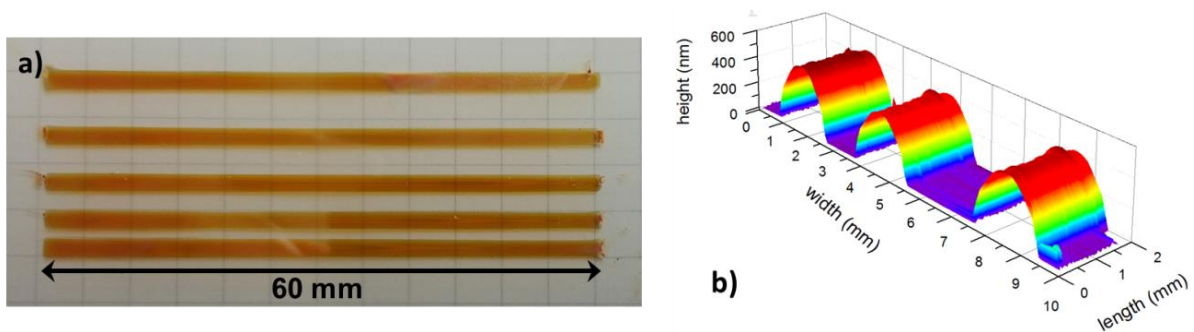


Figure 2 – a) Picture of the patterned deposition on Corning glass using Electrode A and the 2.5 mm wide slits. B) 3D mapping obtained from profilometry measurement on the lines deposited from the 2.5 mm wide slits.

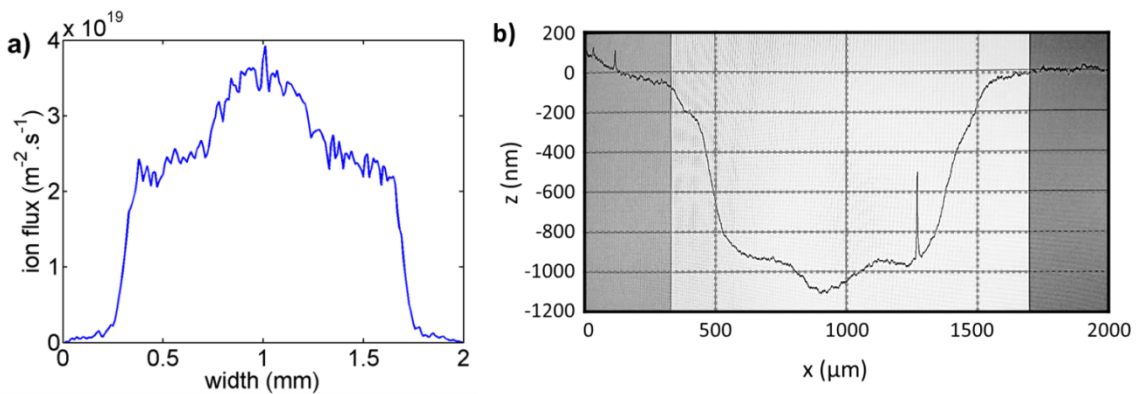


Figure 3 – a) Result of PIC simulation of the cycle-averaged ion flux at the substrate surface in argon plasma. b) Profilometry scan of a crystalline silicon wafer etched by an argon/hydrogen plasma.